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(71) Applicant: **ILLUMINA, INC.** [US/US]; 5200 Illumina Way, San Diego, California 92122 (US).

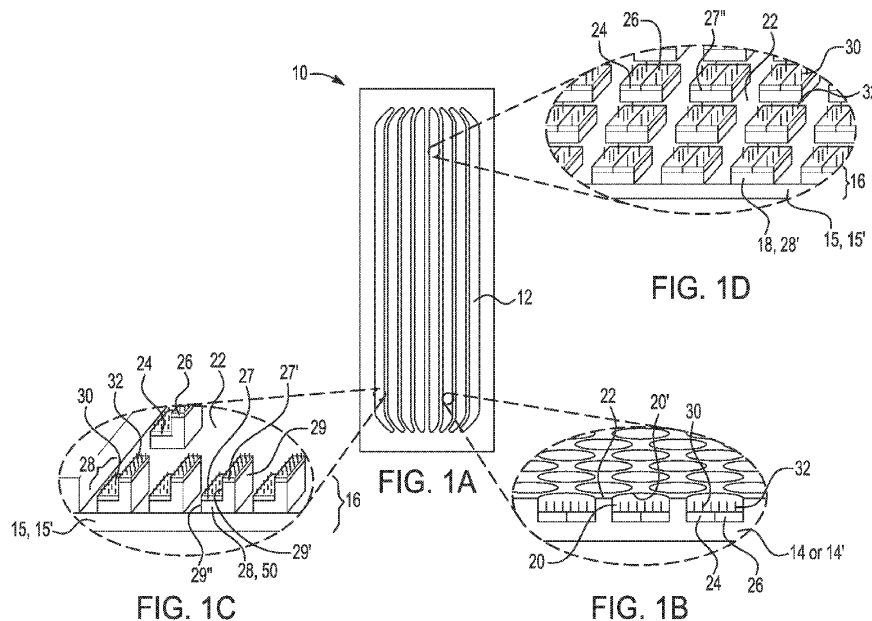
(72) Inventors: **FISHER, Jeffrey S.**; 5200 Illumina Way, San Diego, California 92122 (US). **GHONGE, Tanmay**; 5200

Illumina Way, San Diego, California 92122 (US). **HONG, Sahngki**; 5200 Illumina Way, San Diego, California 92122 (US). **KRAFT, Lewis J.**; 5200 Illumina Way, San Diego, California 92122 (US).

(74) Agent: **DIERKER, Julia Church** et al.; Dierker & Kavanaugh, P.C., 3331 W. Big Beaver Road, Suite 109, Troy, Michigan 48084 (US).

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(54) Title: FLOW CELLS AND METHODS FOR MAKING THE SAME



(57) Abstract: In a method, a resin layer of a stack (e.g., resin layer over sacrificial layer over transparent substrate) is imprinted to form a convex region including first region with first height and second region with second height < first height. Stack portions are etched around the convex region to expose a substrate portion. The stack is utilized to develop a curable layer to define a cured layer over the exposed substrate portion. The convex region and cured layer are etched. The resin layer and a sacrificial layer portion underlying the second region are removed. A second substrate portion is exposed and a third substrate portion remains covered by a remaining sacrificial layer portion. The cured layer is substantially co-planar with the remaining sacrificial layer portion. A depression is formed extending to the second substrate portion. The remaining sacrificial layer portion is utilized to define functionalized layers over different depression regions.

[Continued on next page]

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